

Low-pressure plasma system

V15-G

Stand-alone system

The system is integrated in a 19" rack, which is equipped with rollers and height-adjustable feet. A professional PLC control unit serves as a storage for definable process parameters.

Technical data

Outer dimensions: approx. W 620 x H 1,850 x D 900 mm
Inner dimensions process chamber: approx. W 250 x H 250 x D 250 mm
Microwave power generator: 2.45 GHz, from 100 up to max. 600 W
Gas supply: 1 gas channel with mass flow controller and magnetic valve
Vacuum connection: DN 25 ISO-KF
Electrical connection: 230/400 V, 50/60 Hz, 1.5 kW, 16 A (without vacuum pump)
Process control: PLC control unit (PP 420 by B & R)
Vacuum gauge: Pirani
Surface treatment methods: cleaning, activation, coating (optional)

Available options

- Vacuum pump
- Ozone trap
- Further gas channels (up to max. 4)
- Rotating drum for bulk material treatment
- Rotating table
- Ethernet interface
- Exhaust gas scrubber
- Liquiflow controller
- Chamber liner
- Soft-start and slow-vent
- 8-pin standard paper printer
- Further frequencies (kHz, MHz) possible
- Rack with shelves
- Further options on request



The standard system V15-G is designed as a stand-alone unit for the industrial small series production as well as for the low-pressure plasma treatment in R&D laboratories.

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